

AMENDMENTS TO THE CLAIMS

Please cancel claims 12 and 14 and amend claims 11, 13, and 15-17, such that the status of the claims is as follows:

1. (Withdrawn) A deposition system for oblique deposition comprising:
 - a source of vaporized species traveling at a first distribution of angles surrounding an oblique angle θ measured relative to a surface normal of a substrate;
 - a shadow mask including at least one aperture located between the source and a substrate wherein the shadow mask intercepts a portion of the vaporized species traveling at the first distribution thereby limiting the vaporized species passing through the aperture to traveling at a second distribution of angles surrounding an oblique angle θ ; and
 - the substrate contacted by the second distribution of vaporized species, the species forming a tilted thin film on the substrate.
2. (Withdrawn) The deposition system of claim 1 wherein the source of vaporized species is a physical vapor deposition source.
3. (Withdrawn) The deposition system of claim 1 wherein the oblique angle θ is greater than 35° and less than 90° .
4. (Withdrawn) The deposition system of claim 1 wherein the oblique angle θ is greater than 55° and less than 75° .

5. (Withdrawn) The deposition system of claim 1 wherein the shadow mask limits the vaporized species traveling through the aperture so as to organize the angles of the vaporized species thereby forming a tilted thin film having azimuthal symmetry.
 6. (Withdrawn) The deposition system of claim 1 wherein the shadow mask limits the vaporized species traveling through the aperture so as to organize the angles of the vaporized species into a circumferential pattern.
 7. (Withdrawn) The deposition system of claim 1 wherein the shadow mask limits the vaporized species traveling through the aperture so as to organize the angles of the vaporized species into a radial pattern.
 8. (Withdrawn) The deposition system of claim 1 wherein the aperture has width and the width is non-constant from a first end to a second end.
 9. (Withdrawn) The method of claim 1 wherein the substrate is a circular disc for a recording media.
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10. (Withdrawn) The deposition system of claim 1 wherein the shadow mask has at least two apertures.
 11. (Currently Amended) A method for oblique deposition onto a substrate, the method comprising:
directing vaporized species from a vapor source positioned at an oblique angle to the substrate toward [[a]] the substrate at a distribution of angles of incidence about an angle θ measured relative to a surface normal of the substrate;
rotating the substrate about an axis of rotation while depositing the vaporized species on the substrate; and

narrowing the ~~angular distribution~~ distribution of angles of incidence by permitting only a portion of the vaporized species traveling at approximately the angle θ to pass through an aperture in a shadow mask positioned between the vapor source and the substrate, wherein the aperture extends in a radial direction with respect to the axis of rotation of the substrate.

12. (Canceled)

13. (Currently Amended) The method of claim 11 wherein the distribution of ~~[[the]]~~ angles of incidence is narrowed by intercepting a portion of the vaporized species not traveling at about the angle θ , wherein the species are intercepted with ~~[[a]]~~ the shadow mask.

14. (Canceled)

15. (Currently Amended) The method of claim ~~[[14]]~~ 11 comprising the additional step of forming a single continuous film of the vaporized species wherein the distribution of angles of incidence of the vaporized species are organized into azimuthal symmetry.

16. (Currently Amended) The method of claim ~~[[14]]~~ 11 comprising the additional step of forming a single continuous film of the vaporized species wherein the distribution of angles of incidence of the vaporized species are organized into a circumferential pattern.

17. (Currently Amended) The method of claim ~~[[14]]~~ 11 comprising the additional step of forming a single continuous film of the vaporized species wherein the distribution of angles of incidence of the vaporized species are organized into a radial pattern.

18. (Withdrawn) A shadow mask for oblique deposition by physical vapor deposition onto a substrate, the shadow mask comprising a slot aperture, the slot aperture having generally radial direction relative to a circular substrate.

19. (Withdrawn) The device of claim 18 wherein the aperture has width and the width is non-constant from a first end to a second end.

20. (Withdrawn) The shadow mask of claim 18 comprising a plurality of slot apertures separated by walls adjacent to the shadow mask.
